LISTING OF THE CLAIMS

A detailed listing of all claims that are, or were, in the present application, irrespective of whether the claim(s) remains under examination in the application are presented below. The claims are presented in ascending order and each includes one status identifier. Those claims not cancelled or withdrawn but amended by the current amendment utilize the following notations for amendment: 1. deleted matter is shown by strikethrough for six or more characters and double brackets for five or less characters; and 2. added matter is shown by underlining.

1. - 9. (Cancelled).

- 10. (Previously Presented) A method of producing a structured hard chrome layer, comprising electrodepositing chromium from an electrolyte onto a workpiece, said electrolyte comprising:
- (a) a Cr (VI) compound in an amount corresponding to 50 g/l to 600 g/l of chromic acid anhydride;
 - (b) 0.5 g/l to 10 g/l of sulphuric acid;
 - (c) 1 g/l to 20 g/l of aliphatic sulphonic acid, that comprises 1 to 6 carbon atoms, and
- (d) 10 g/l to 200 g/l of at least one compound forming a dense cathode film, said compound being selected from the group consisting of ammonium molybdate, alkali molybdate, alkaline earth molybdate, ammonium vanadate, alkali vanadate, alkaline earth vanadate, ammonium zirconate, alkali zirconate, and alkaline earth zirconate,

wherein the cathodic current yield in the production of the structured hard chrome layer is 12% or less, such that said hard chrome layer comprises at least one of a cup-shaped structure, a labyrinth structure, or a column-shaped structure.

- (Previously Presented) The method as claimed in claim 10, wherein the Cr(VI) compound is CrO₃.
- (Previously Presented) The method of claim 10, wherein the aliphatic sulphonic acid is methane sulphonic acid.

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- (Previously Presented) The method of claim 10, wherein the compound forming a dense cathode film is (NH₄)₆Mo₇O₂₄ 4 H₂O.
- (Previously Presented) The method of claim 10, wherein the electrolyte comprises substantially no fluorides.
- (Previously Presented) The method of claim 10, which further comprises applying a current density of from 20 A/dm² to 200 A/dm² to the workpiece.
- 16.-21. (Cancelled).